



Call for Papers – DPS 2016

38th International Symposium on Dry Process

November 21(Mon) – 22(Tue), 2016

Conference Hall, Hokkaido University,
Sapporo, Hokkaido, Japan



Paper Submission Deadline: July 15, 2016

Author instructions and information about DPS can be found at:

<http://www.dry-process.org/2016/>

The 38th International Symposium on Dry Process (DPS2016) will be held at Conference Hall, Hokkaido University, Sapporo, Hokkaido, in Japan, on November 21 & 22, 2016. The Symposium covers all aspects of the rapidly evolving fields of dry processes, including but not limited to plasma etching and deposition processes, diagnostics and modeling of plasmas and surfaces, and surface modifications by plasmas, for the applications in, e.g., microelectronics, power devices, sensors, environmental protection, biological systems, and medicine. The DPS has provided valuable forums for in-depth discussion among professionals and students working in this exciting field for more than three decades.

Theme: Dry processes and related technologies from fundamentals to applications

Topics:

1. Etching Technology
2. Manufacturing Technology (AEC, APC, EES, FDC)
3. Surface Reaction and Damage
4. Plasma Diagnostics and Monitoring System
5. Modeling and Simulation
6. Plasma Generation (Equipment/Source)
7. CVD / PVD / ALD
8. Plasma Processes for 3D Device, FPD, Photovoltaic Devices
9. Plasma Processes for New Material Devices (MRAM, Power, Organic)
10. Plasma Processes for Biological and Medical application, MEMS
11. Atmospheric Pressure Plasma and Liquid Plasma Process Concepts
12. New Dry Process Concepts

Arranged session:

- A1. How can we control atomic layer reactions ? (ALE/ALD)
- A2. Modeling and simulation for precise reaction control

For further general information, please contact:

e-mail: dps2016@officepolaris.co.jp

Organizing Committee Chair: Tetsuya Tatsumi (Sony Corp.)
Executive Committee Chair: Koichi Sasaki (Hokkaido University)
Program Committee Chair: Masanobu Honda (Tokyo Electron Ltd.)
Publication Committee Chair: Kenji Ishikawa (Nagoya University)

URL: <http://www.dry-process.org/2016/>

DPS 2016 is co-sponsored by The Japan Society of Applied Physics

